AMENDMENTS TO THE CLAIMS

1. (original)An electrode substrate, comprising:

a substrate;

a first electrode disposed on the substrate; and

a pixel-defining layer with waved sidewalls disposed on the first electrode or on the substrate.

2. (original)The electrode substrate of claim 1, wherein the substrate is at least one selected from the group consisting of a glass substrate, a plastic substrate, and a flexible substrate.

3. (original)The electrode substrate of claim 1, wherein the first electrode is a conductive metal oxide electrode.

4. (original)The electrode substrate of claim 1, wherein the first electrode is at least one selected from the group consisting of an indium-tin oxide (ITO) electrode and an aluminum-zinc oxide (AZO) electrode.

5. (original)The electrode substrate of claim 1, wherein the pixel-defining layer is made of a non-conductive material.

6. The electrode substrate of claim 5, wherein the pixel-defining layer is a photoresist.

7. (original)The electrode substrate of claim 6, wherein the photoresist is photosensitive polyimide.

8. (original)The electrode substrate of claim 6, wherein the photoresist is photosensitive diazonaphtho-quinone-phenolic resin.

9. (original)A method for manufacturing an electrode substrate, comprising:

forming a first electrode on a substrate; and

forming a pixel-defining layer with waved sidewalls on the first electrode or on the substrate.

10. (original) The method of claim 9, wherein the substrate is at least one selected from the group consisting of a glass substrate, a plastic substrate, and a flexible substrate.

11. (original) The method of claim 9, wherein the first electrode is conductive metal oxide electrode.

12. (currently amended) The method of claim 9~~2~~, wherein the pixel-defining layer is made of a non-conductive material.

13. (original) The method of claim 9, wherein the waved sidewalls of the pixel-defining layer is formed by an exposure process and a development process, wherein the exposure process uses a standing wave effect produced by an light beam to expose the pixel-defining layer, and the development process then develops the pixel-defining layer to form the pattern.

14. (original) The method of claim 9, wherein the pattern of the sidewall of the pixel-defining layer is saw-toothed.

15. (original) The method of claim 9, wherein the pattern of the sidewall of the pixel-defining layer is undulated.

16. (original) The method of claim 9, wherein the pattern of the sidewall of the pixel-defining layer is irregular.

17. (original) An organic electroluminescent panel, comprising:

a substrate;

a first electrode formed on the substrate;

a pixel-defining layer with waved sidewalls disposed on the first electrode or on the substrate;

an organic functional layer disposed on the first electrode; and

a second electrode disposed on the organic functional layer.

18. (original) The organic electroluminescent panel of claim 17, wherein the pixel-defining layer is non-conductive.

19. (original) The organic electroluminescent panel of claim 18, wherein the pixel-defining layer is a photoresist.

20. (original) The organic electroluminescent panel of claim 19, wherein the photoresist is photosensitive polyimide.

21. (original) The organic electroluminescent panel of claim 19, wherein the photoresist is photosensitive diazonaphtho-quinone-phenolicresin.